



# LINAC 4 H<sup>-</sup> Source RF System

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**LINAC 4 H<sup>-</sup> Source RF System  
and Measurement of RF power  
Coupling to the Plasma.**



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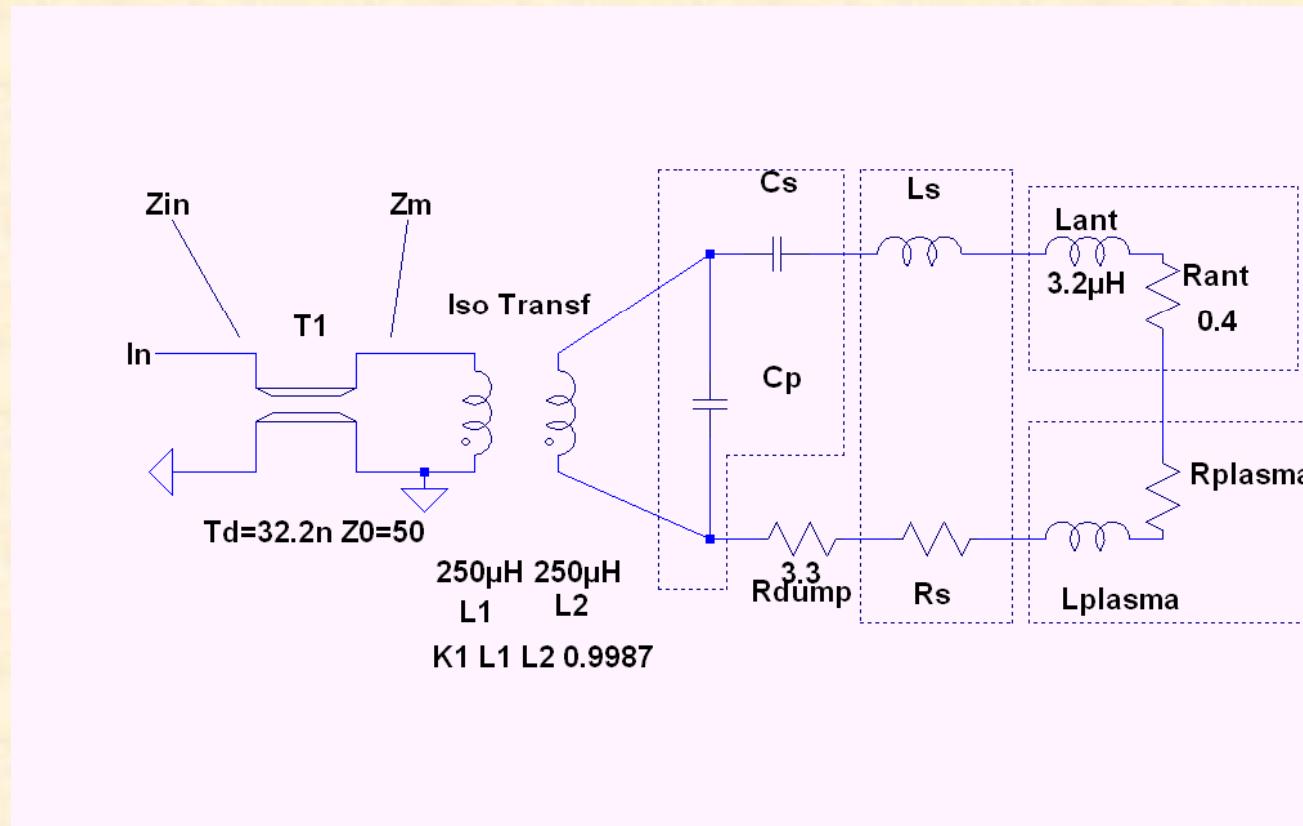
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- **2ms pulses, 2Hz rep. rate (50Hz in future SPL)**
- **All equipment grounded.**
- **Wideband solid-state drivers.**
- **2MHz ±200 kHz, 100 kW final stage.**
- **Isolation transformer : wideband, 1÷1 device**
- **Capacitive matching network with adjustable inductance for tuning.**
- **Adjustable frequency agile operation.**
- **AVC loop stabilizes the FWD power.**



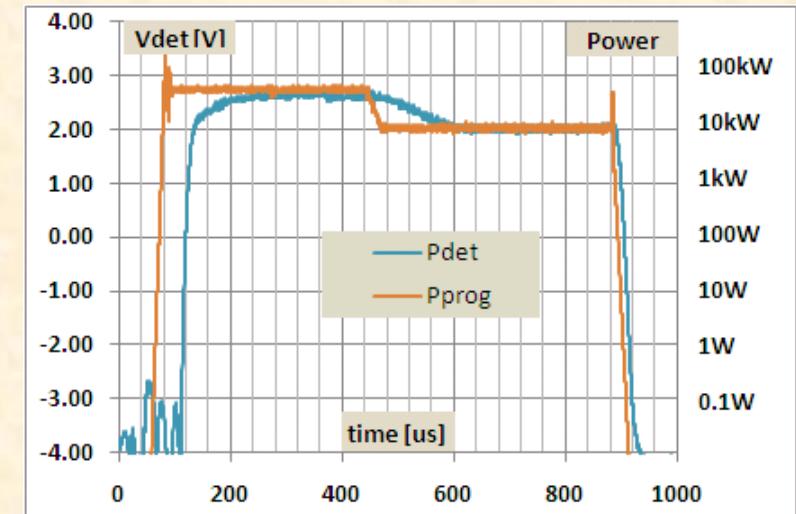
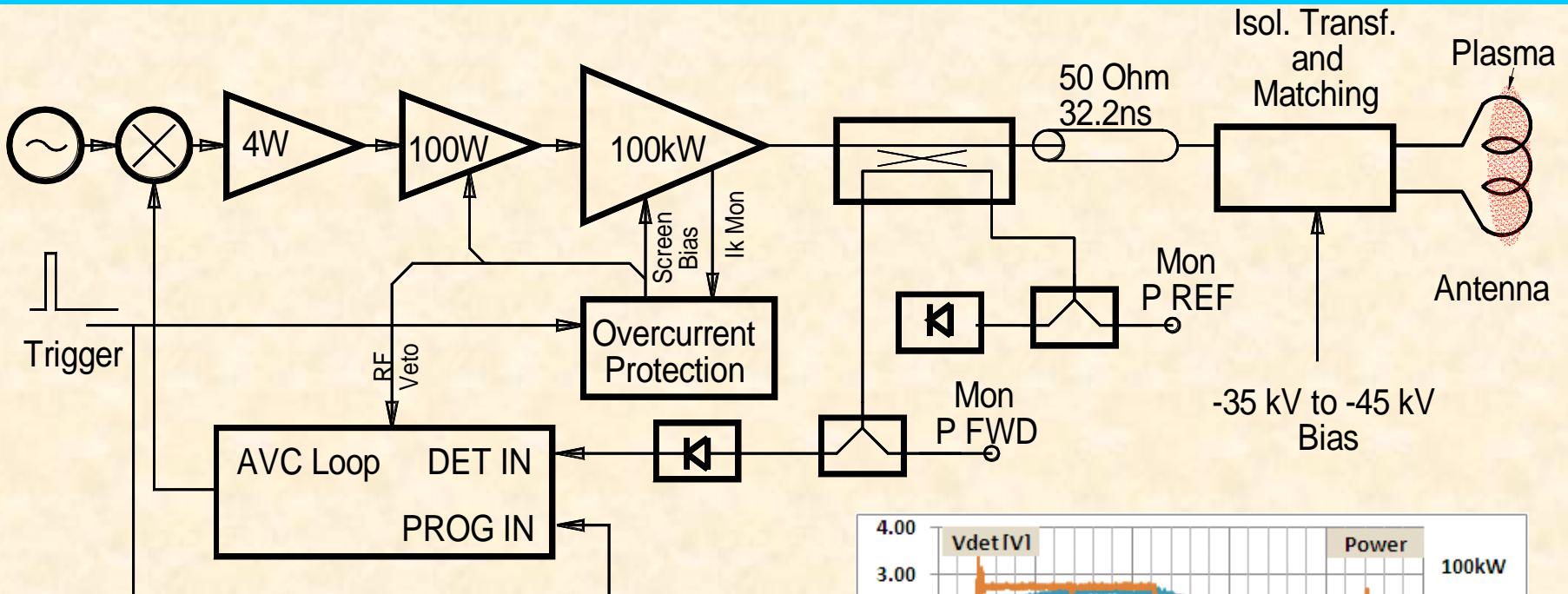
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## Antenna, matching network and connection line



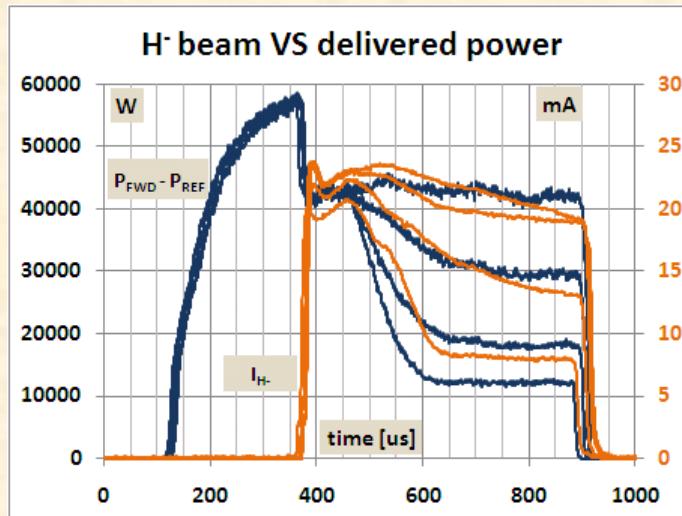
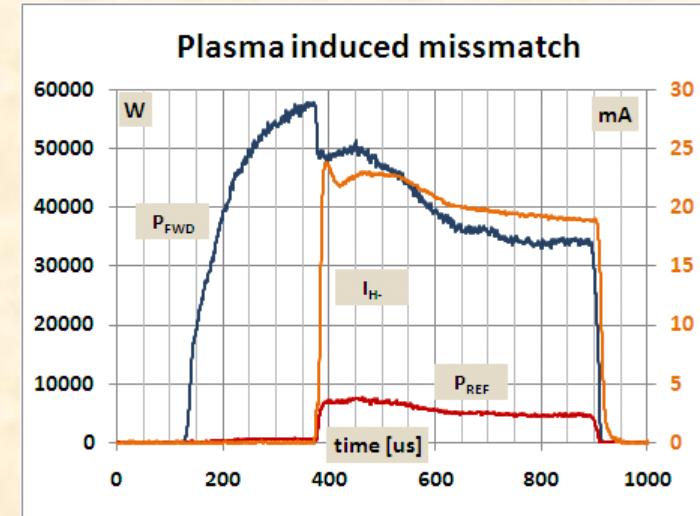
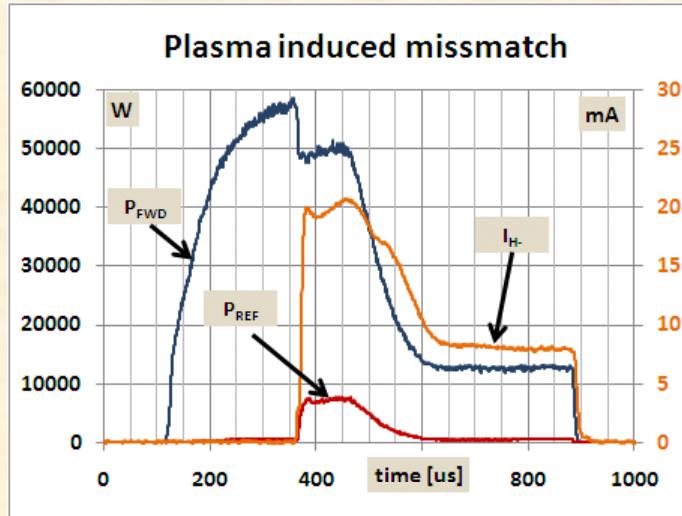


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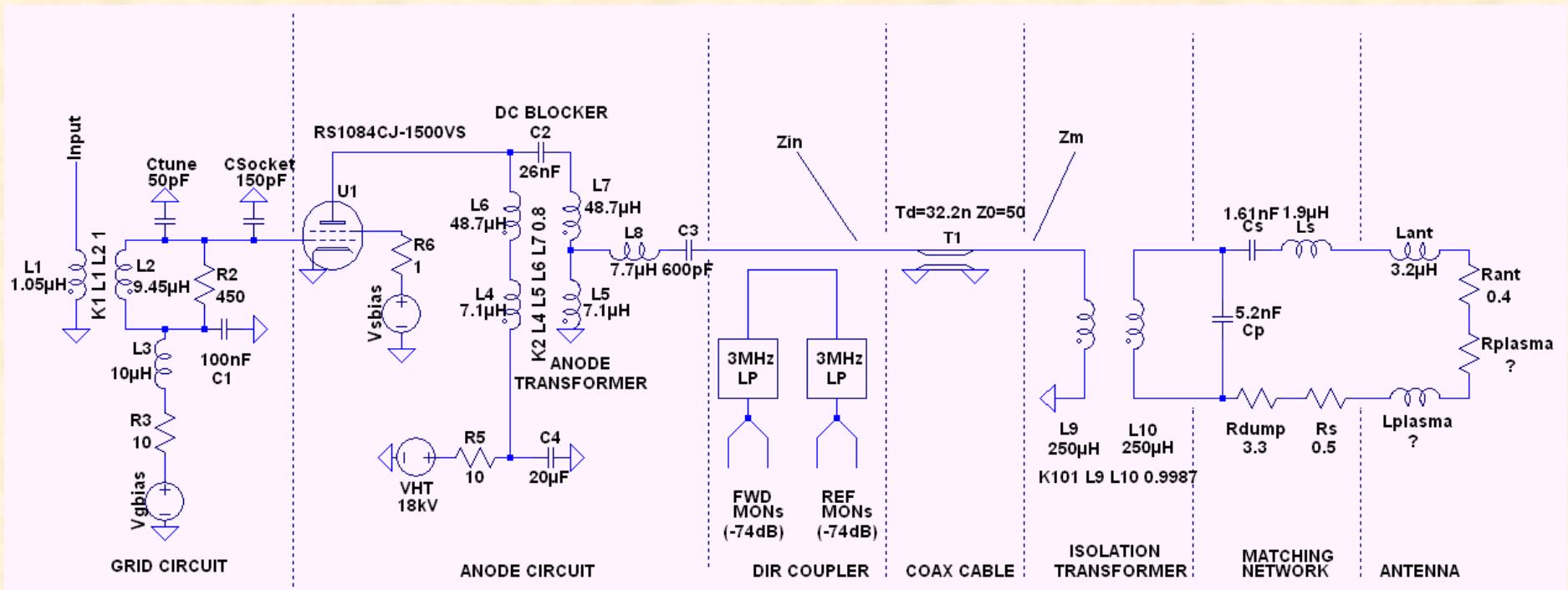


How can we estimate the power delivered to the plasma and the plasma impedance?



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## Power section of the system.



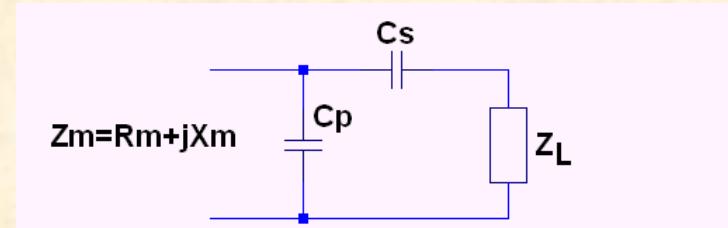


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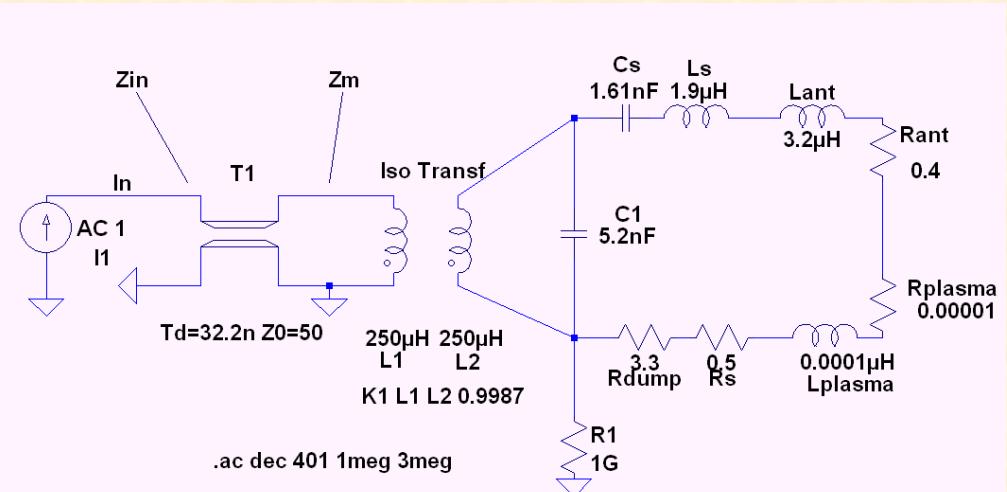
From measured forward and reflected signals the complex reflection coefficient can be computed.

Then, knowing the circuit components, the antenna impedance can be worked out...

... either analytically...



... or with Spice simulations.





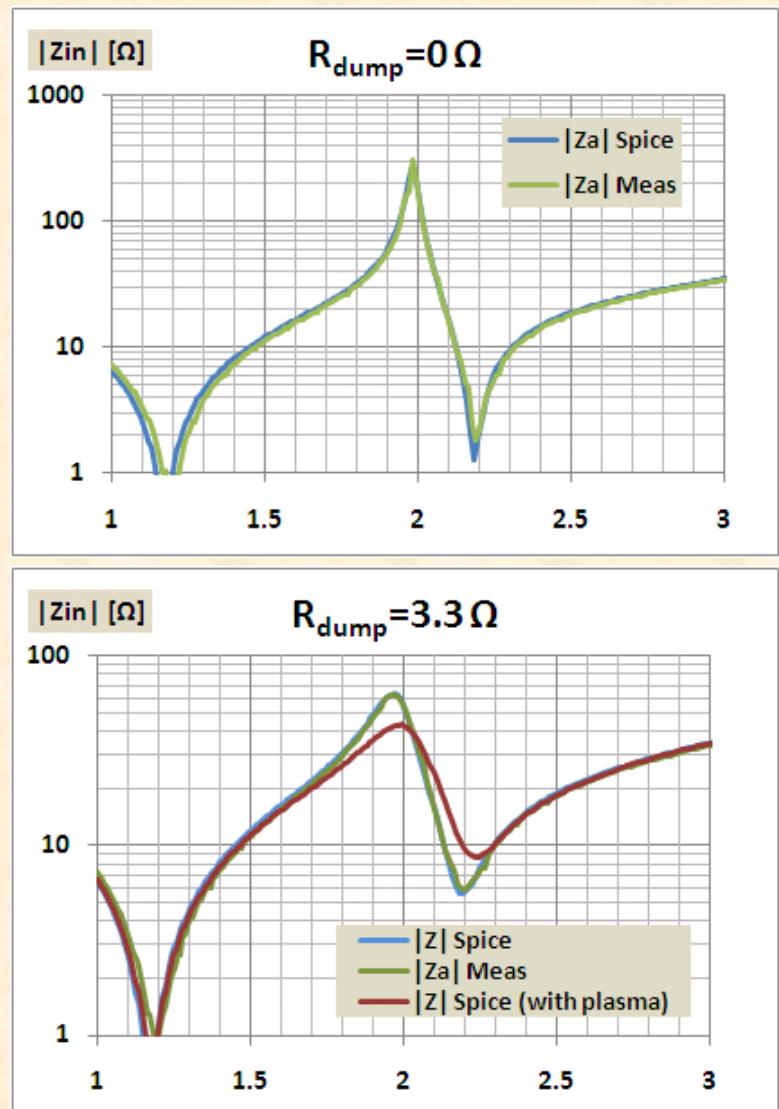
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## SPICE simulation

P <sub>FDW</sub> [kW]	R <sub>plasma</sub> [Ω]	L <sub>plasma</sub> [uH]	P <sub>plasma</sub> [kW]	I <sub>H-</sub> [mA]
24.0	1.8	-0.13	6.9	14
41.2	2.2	-0.21	12.9	19
64.0	2.2	-0.21	20.0	22

## Analytical method

24.0	1.6	-0.13	6.7	14
41.2	1.6	-0.20	11.4	19
64.0	1.6	-0.20	17.8	22





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## Next steps

- Design the matching network for higher efficiency.
- Improve the AVC loop performance.
- Implement a dynamic measurement system of the complex reflection factor.